



Note:

1. SUBSTRATE:IR MONO GRADE SI
2. GROWING METHOD:FZ
3. CLEAR APERTURE:90%
4. SURFACE QUALITY:S1&S2 60-40 SCRATCH-DIG
5. PARALLELISM:1ARCMIN
6. PV: $\lambda/2$
7. COATING:NONE

8 FINE GRIND SURFACE

SPECIFICATIONS SUBJECT TO CHANGE  
WITHOUT NOTICE

FOR INFORMATION ONLY  
NOT FOR MANUFACTURE

DRAWING PROJECTION		ALL DIMS IN	MM
DESIGNED	CHECKED	APPROVED	SCALE
			1:1
MATERIAL	Silicon	TITLE	SI IR-MONO ROUND WINDOW $\phi 25.4 * T3$
本征晶体 INTRINSIC CRYSTAL	www.icc-mall.com	DWG NO	PSI01E011
		EDITION	1ST
		SHEET	1/1